

Focus Tech DV-6450

Developer Concentrate

Product Description

DV-6450 is a highly concentrated developer solution designed for use in photoresist and soldermask developing processes. Formulated using water softening agents, working solutions of DV-6450 can be made using tap water with up to 400 ppm's of dissolved solids without forming significant hardness scale. DV-6450 also contains cleaning compounds that help break up resist residues to prevent deposition and build up in process and control equipment. The Focus Tech developing system combines high quality with ease of use to provide a superior developing system.

Features Benefits

B ● Highly concentrated

Softening agents

Detergent additives

Minimizes handling

© Eliminates need for purified water

Extends uptime by slowing scum build-up

Physical Properties

Concentration: 450 g/L as potassium carbonate

Specific gravity: 1.36 pH: >12

Appearance: clear, water white

Freezing point: <40 °F

Typical Operating Parameters

Make Up: 1.78 – 2.22% v/v DV-6450

8-10 g/L as potassium carbonate

Replenishment: 1.78 – 2.22% v/v DV-6450

8 – 10 g/L as potassium carbonate

Process pH: 10.4 - 10.9Temperature: $80 \,^{\circ}\text{F} - 90 \,^{\circ}\text{F}$

Storage

Store in original containers above 40 °F.

Safety

CAUTION! DV-6450 concentrates and working solutions contain strong alkaline ingredients. Avoid contact with eyes, skin and clothing. Wear chemical handler's gloves, goggles and protective clothing when handling. Read and understand Material Safety Data Sheet before using this product.

Notice

The information and recommendations, contained herein, regarding this product are, to the best of our knowledge, true and accurate. We make no guarantee of results because the conditions of actual use are beyond our control. We assume no liability for damages or penalties resulting from the use of this product or following our recommendations. Our recommendations and suggestions for use of this product are not intended to grant license to operate under or infringe any patent.